

Floating Gate Transistor

Noah Allen

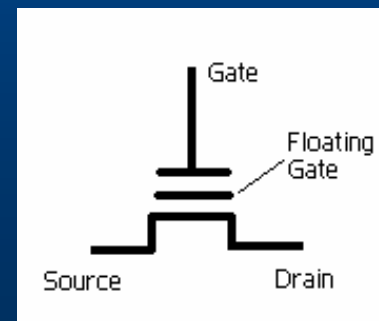
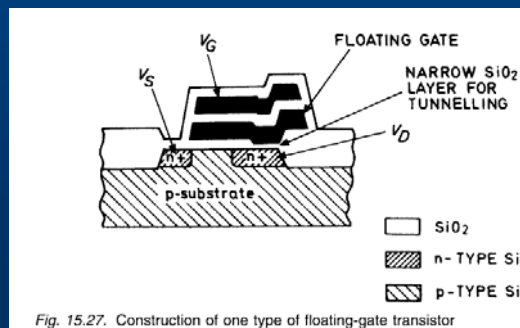
ECE 3080 Presentation

Floating Gate Transistors

- Structure
- Function analysis
- “Readable” and “Writable”
- Use in nonvolatile memory

Introduction

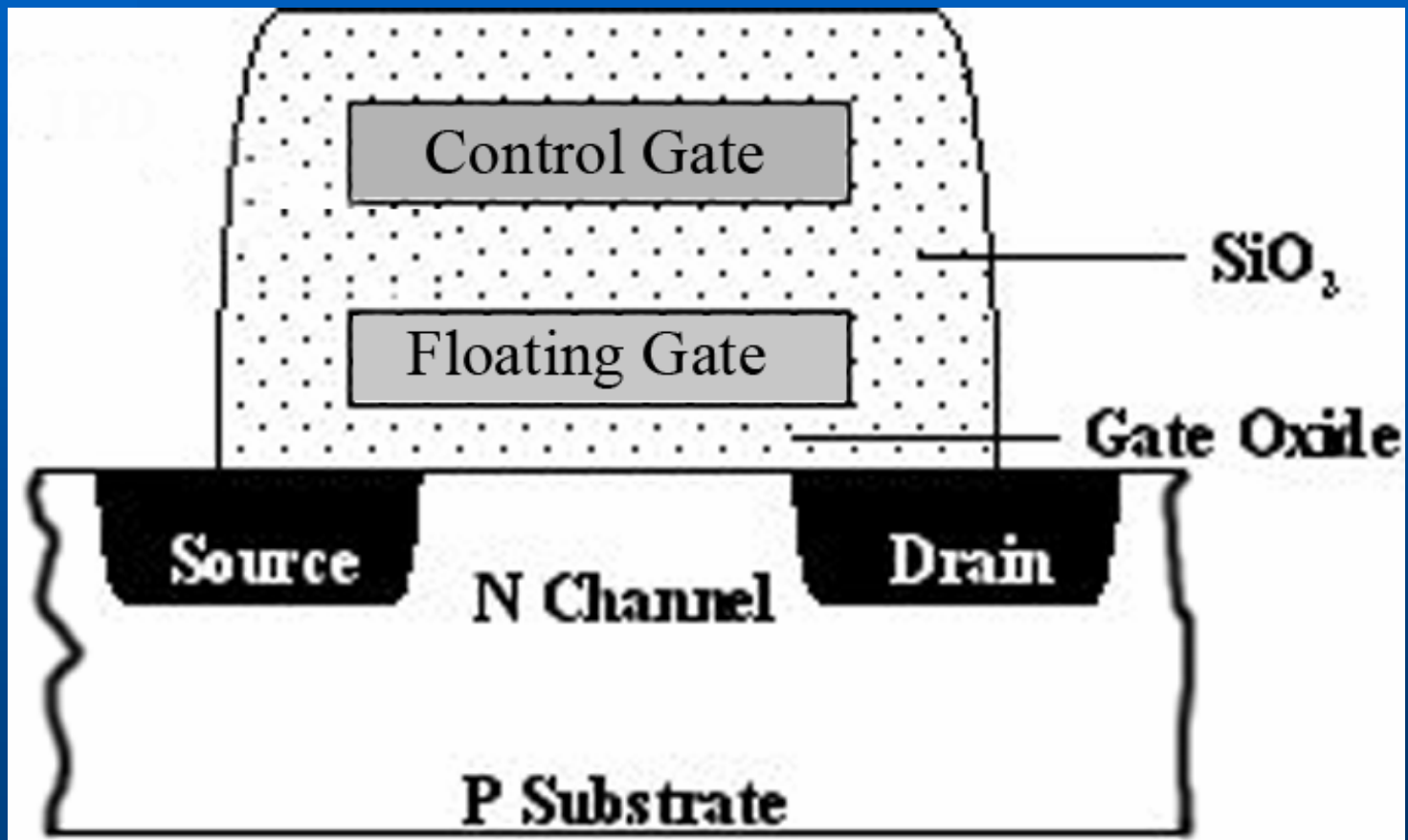
- Works the same way that MOSFET works
- Has extra “floating gate”
- Stores charge on the floating gate
- EPROM and EEPROM



History

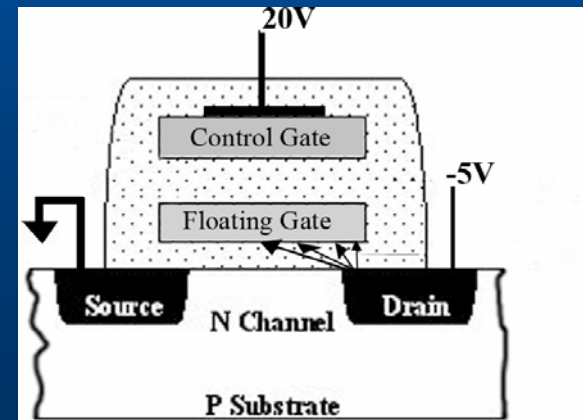
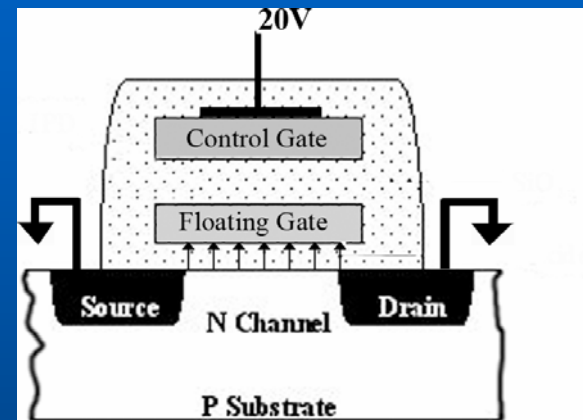
- **Founded by Kahng and Sze (Bell Labs) 1967**
- **EPROM invented by Don Fohman 1971**
- **EEPROM invented by George Perlegos (Intel) 1983**
- **Beginning to move out of memory uses toward neuromorphic systems**

FGMOS Analysis



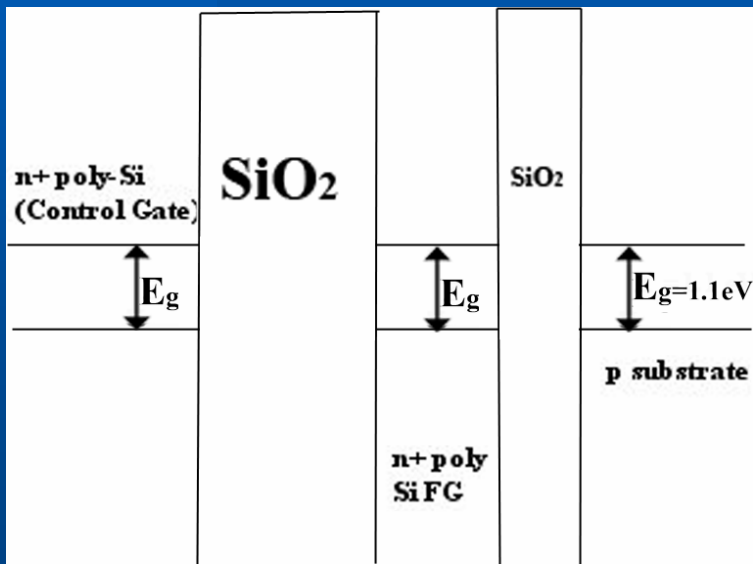
FGMOS: Programming

- **Fowler-Nordheim (FN) Tunneling**
 - Silicon Dioxide layer act as a boundary
 - Large voltage is applied to the Control Gate
 - Voltage create a high electric field
 - Electrons tunnel through thin SiO_2 barrier
 - Thin: 5-12nm Thick: 25-45nm

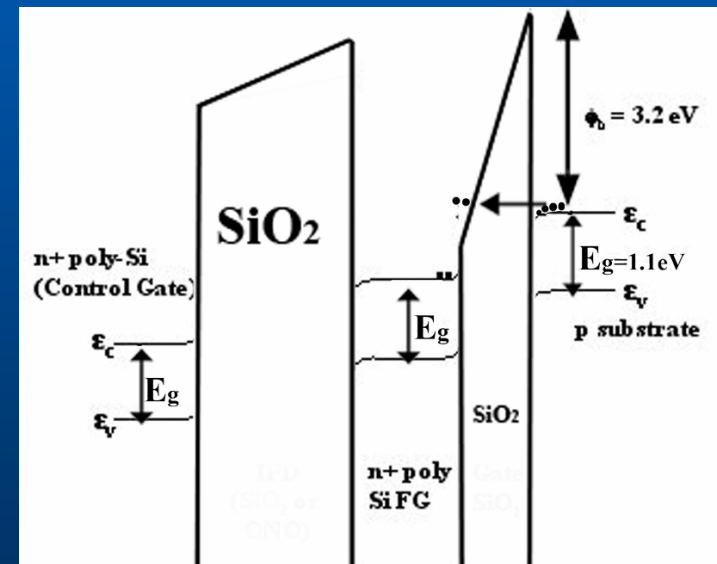


FGMOS: Programming

Normal Band Diagram



*Fowler-Nordheim (FN)
Tunneling Band Diagram*



FGMOS: Programming

$$J = \alpha E^2 \cdot \exp\left(-\frac{\beta}{E}\right)$$

where

$$\alpha = \frac{q^3}{8\pi \cdot \phi_b} \cdot \frac{m}{m^*}$$

$$\beta = 4\sqrt{2m^*} \frac{\phi_b^{\frac{3}{2}}}{3\hbar q}$$

\hbar = Planck's Constant

ϕ_b = Energy Barrier at the injecting surface (3.2 eV for Si - SiO₂)

q = Charge of electron

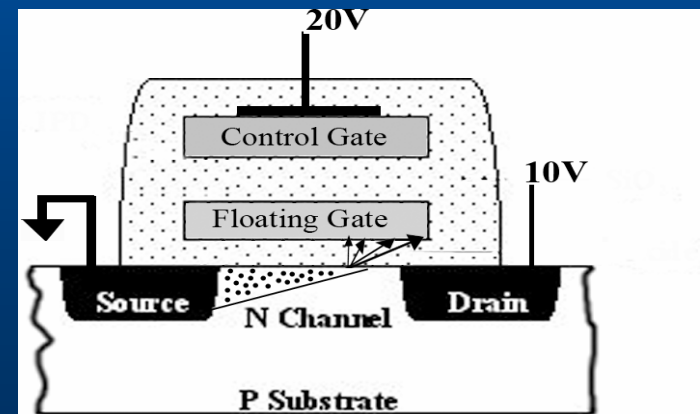
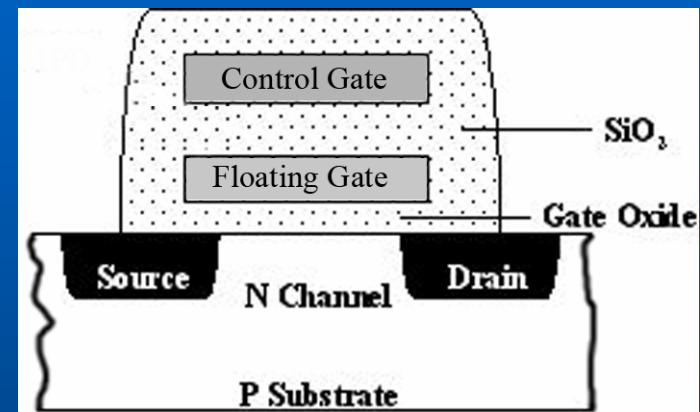
m = Mass of free electron

m^* = Effective Mass of an electron

E = Electric field at the injecting surface

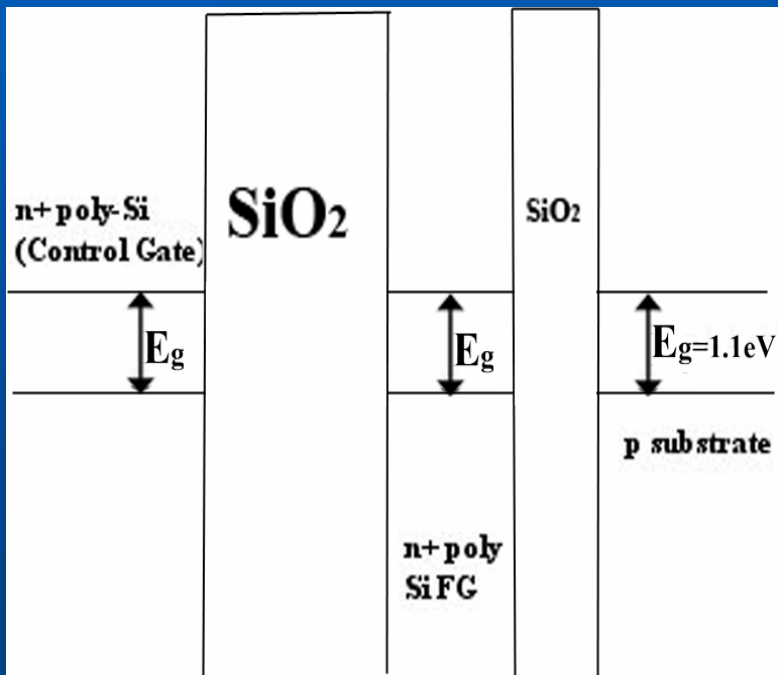
FGMOS: Programming

- **Hot-Carrier Injection (HCI)**
 - Hot Electron injection for N-Type and Hot Hole injection for P-Type (longer for Holes)
 - Drain is biased causing electric field
 - Control gate biased to create second electric field
 - Electrons or holes gain enough energy to exceed energy barrier

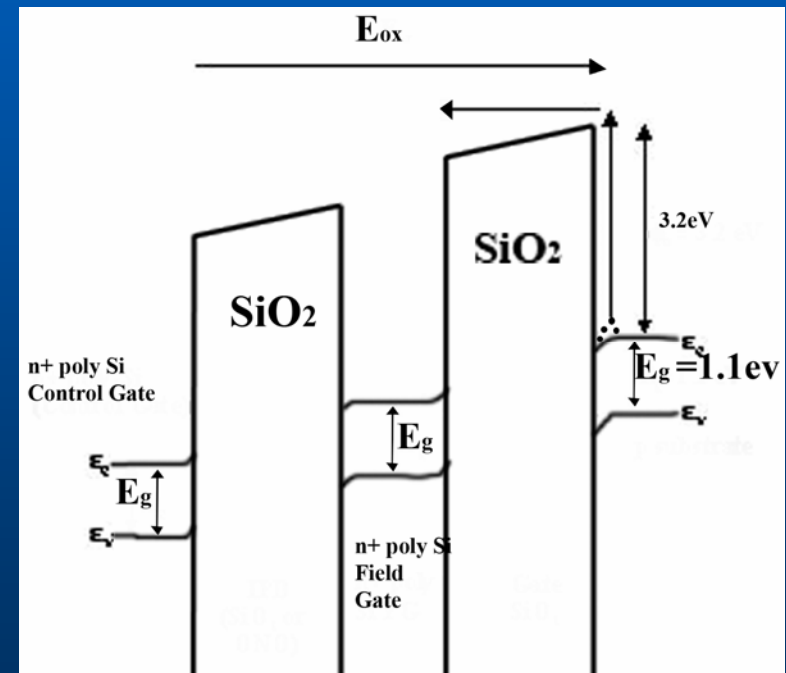


FGMOS: Programming

Normal Band Diagram

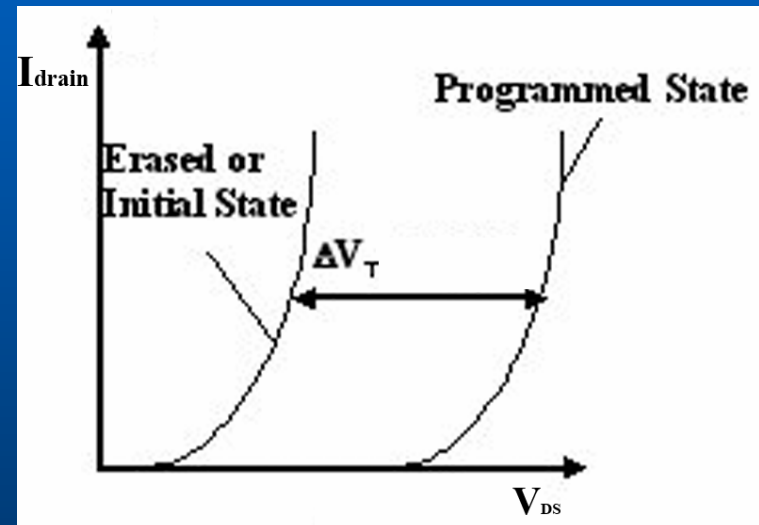


Hot-Electron Injection Band Diagram



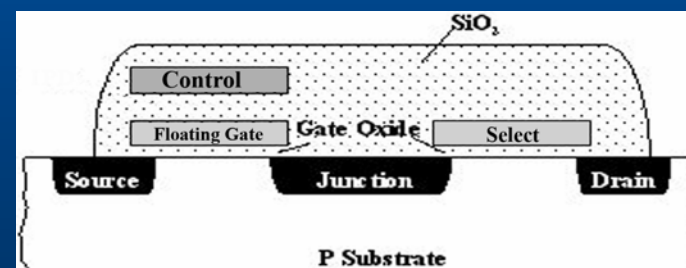
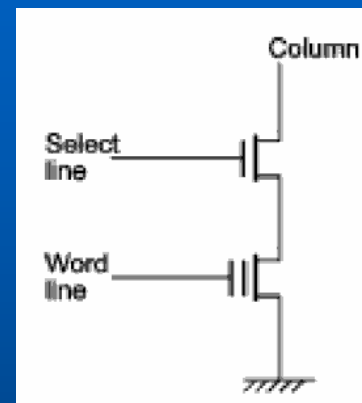
FGMOS: Reading

- Programming
 - Setting the FGMOS to “0”
- Erasing
 - Setting the FGMOS to “1”



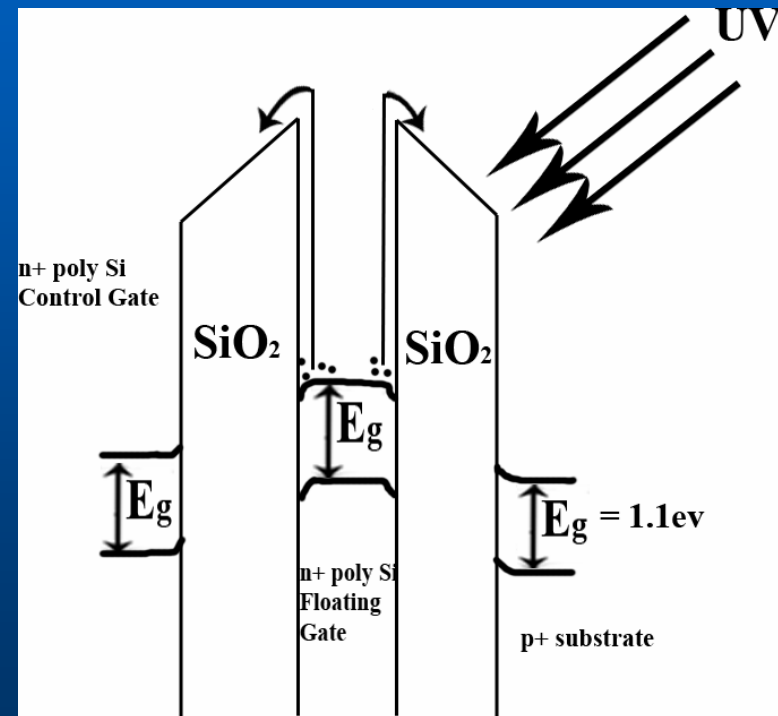
FGMOS: Reading

- Select line is brought high (3.5 V)
- Bit line is brought high (3.5 V)
- Current pulse is sent through column
- Cell sensor detects current pulse

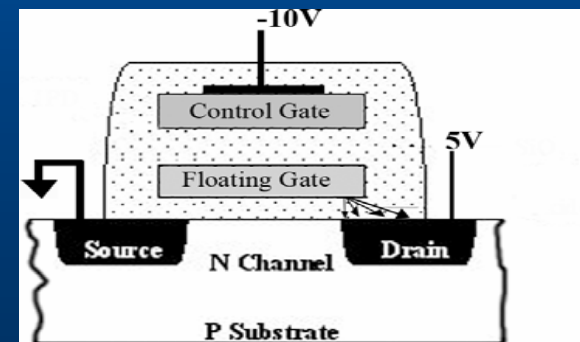
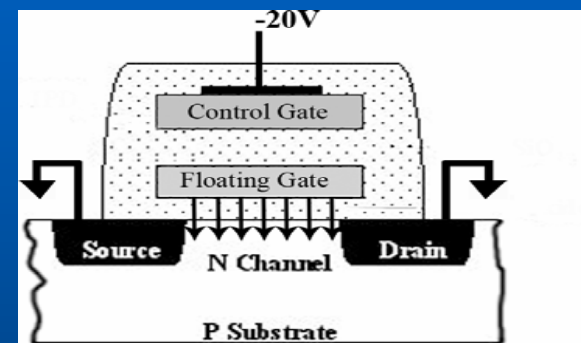
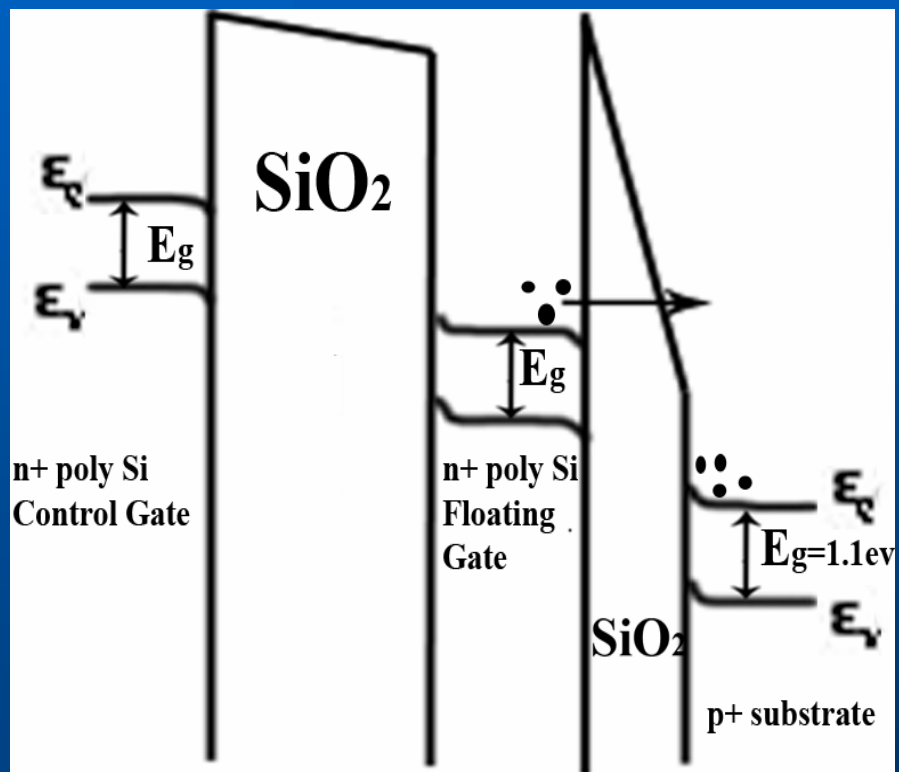


FGMOS: Erasing

- **Erasable Programmable Read Only Memory (EPROM)**
 - Can be individually address and programmed, not erased
 - Use another tool to erase
 - Excites electrons over the insulating barriers
 - UV light at 253.7 nm wavelength most efficient
 - 3 weeks sunlight
 - 1 year fluorescent light
 - 4.5 minutes Germicidal Lightbulb



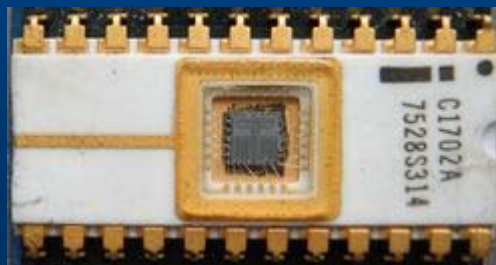
EEPROM: Erasing



EPROM/EEPROM Devices

- EPROM

- Gameboy, Sega Genesis, NES
- Microcontroller
- 10 to 20 year retention



- EEPROM

- Flash Drives
- SSD Hard Disks
- SPI, I2C, 1-Wire
- 10 years or more retention



Questions?

- [1] Stanley William Amose and Mike James, "Principle of Transistor Circuits: Intro to the Design of Amplifier" pp323-325
- [2] Jitu J. Makwana and Dr. Dieter K. Schroder, "A Nonvolatile Memory Overview"
– <http://aplawrence.com/Makwana/nonvolmem.html>
- [3] Paul Hasler, Bradley Minch and Chris Diorio, "Floating-Gate Devices: They Are Not Just For Digital Memories Anymore"
- [4] Edgar Sanchez-Sinencio, "Floating Gate Techniques and Applications",
<http://amesp02.tamu.edu/~sanchez/607-2005-Floating%20Gate%20Circuits.pdf>
- [5] "EPROM." *Wikipedia, The Free Encyclopedia*. 30 Mar 2008, 02:28 UTC. Wikimedia Foundation, Inc. 14 Apr 2008 <<http://en.wikipedia.org/w/index.php?title=EPROM&oldid=201956136>>.
- [6] "EEPROM." *Wikipedia, The Free Encyclopedia*. 11 Apr 2008, 19:08 UTC. Wikimedia Foundation, Inc. 14 Apr 2008 <<http://en.wikipedia.org/w/index.php?title=EEPROM&oldid=204977559>>.
- [7] "Floating-gate transistor." *Wikipedia, The Free Encyclopedia*. 10 Mar 2008, 07:06 UTC. Wikimedia Foundation, Inc. 14 Apr 2008 <http://en.wikipedia.org/w/index.php?title=Floating-gate_transistor&oldid=197181021>.